

Ion channeling for strain analysis in buried nanofilms (

Citation for published version (APA):

Selen, L. J. M., Janssen, F. J. J., IJzendoorn, van, L. J., Voigt, de, M. J. A., Theunissen, M. J. J., Smulders, P. J. M., & Eijkemans, T. J. (2002). Ion channeling for strain analysis in buried nanofilms (. *Journal of Applied Physics*, 91(8), 5507-5507.

Document status and date:

Published: 01/01/2002

Document Version:

Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

Please check the document version of this publication:

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Erratum: "Ion-channeling analysis of boron clusters in silicon" [*J. Appl. Phys.* **90**, 4741 (2001)]

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[DOI: 10.1063/1.1463446]

The title of the paper should have been: "Ion channeling for strain analysis in buried nanofilms (<6 nm)." In addition, three references appeared incorrectly; corrected versions of Refs. 1, 7, and 13 follow:

¹B. D. Cullity, *Elements of X-Ray Diffraction* (Addison-Wesley, Reading, MA, 1976).

⁷T. C. Q. Noakes, P. Baily, P. K. Hucknall, K. Donovan, and M. A. Howson, *Phys. Rev. B* **58**, 4934 (1998).

¹³J. Lindhard and K. Dan., *Vidensk. Selsk. Mat. Fys. Medd.* **1965**, 34.

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